

<u>S12978</u> U USPT ('6740853' '6780374')!.PN. and heat\$2 and (distanc\$3 or adjust\$3)	2004-10- 26 08:59:04
<u>S12977</u> U USPT ('6740853' '6022418' '6780374')!.PN. and fluid\$2 and (hole\$2 or apertur\$2 or tub\$3) and (pressur\$3 or density) and thermal\$2 near (conducti\$3 or conductanc\$3)) and (distanc\$3 or adjust\$3)	2004-10- 26 08:55:03
<u>S12976</u> U USPT ('6740853' '6022418' '6780374')!.PN. and fluid\$2 and (hole\$2 or apertur\$2 or tub\$3) and (pressur\$3 or density) and thermal\$2 near (conducti\$3 or conductanc\$3)	2004-10- 26 00:20:57
<u>S12975</u> U USPT ('6740853' '6022418')!.PN. and (quart\$3 or al or alumina or sapphire or aluminum or carbon or silicon\$2) and heat\$2	2004-10- 25 22:26:53
<u>S12974</u> U USPT ('6780374' '6740853' '6022418')!.PN. and (quart\$3 or al or alumina or sapphire or aluminum or carbon or silicon\$2)	2004-10- 25 22:24:03
<u>S12973</u> U USPT (((6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and gas\$3) and (quart\$3 or al or alumina or sapphire or aluminum or carbon or silicon\$2)	2004-10- 25 22:23:14
<u>S12972</u> U USPT (thermal\$2 near (processing or proces\$3 or apparatus) and wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4) and fluid\$2 and (hole\$2 or apertur\$2 or tub\$3) and (platinim\$2 or pt)	2004-10- 25 22:15:34
<u>S12971</u> U USPT ('6740853' '6022418' '6780374')!.PN. and (platinim\$2 or pt)	2004-10- 25 22:13:42
<u>S12970</u> U USPT ('6740853' '6022418' '6780374')!.PN. and fluid\$2 and (hole\$2 or apertur\$2 or tub\$3) and heater\$2	2004-10- 25 22:06:13
<u>S12969</u> U USPT ('6740853' '6022418' '6780374')!.PN. and fluid\$2 and (hole\$2 or apertur\$2 or tub\$3)	2004-10- 25 22:02:31
<u>S12968</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and gas\$3	2004-10- 25 14:33:59
<u>S12967</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and pressur\$3 and (HE or helium\$3)	2004-10- 25 14:25:19
<u>S12966</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and (HE or helium\$3)	2004-10- 25 14:24:13

<u>S12965</u> U USPT ('6780374')!.PN. and pressur\$3	2004-10- 25 14:23:34
<u>S12964</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and (control\$3 or comupter\$2) and pressur\$3	2004-10- 25 14:22:56
<u>S12963</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and (control\$3 or comupter\$2) and fluid\$3	2004-10- 25 13:53:06
<u>S12962</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and (control\$3 or comupter\$2)	2004-10- 25 13:50:58
<u>S12961</u> U USPT (((('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and thermal\$2 near (conducti\$3 or conductanc\$3) and (contorl\$3 or computer\$2 or pressur\$3 or inject\$3)) and (control\$3 or comupter\$2)	2004-10- 25 13:49:38
<u>S12960</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and thermal\$2 near (conducti\$3 or conductanc\$3) and (contorl\$3 or computer\$2 or pressur\$3 or inject\$3)	2004-10- 25 11:16:10
<u>S12959</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) and thermal\$2 near (conducti\$3 or conductanc\$3)	2004-10- 25 11:15:11
<u>S12958</u> U USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4) thermal\$2 near (conducti\$3 or conductanc\$3)	2004-10- 25 11:14:58
<u>S12957</u> U USPT ('6780374')!.PN. and (contorl\$3 or computer\$2 or pressur\$3 or inject\$3)	2004-10- 25 11:13:39
<u>S12956</u> U USPT ('6780374')!.PN. and fluid\$3 and (contorl\$3 or computer\$2 or pressur\$3 or inject\$3)	2004-10- 25 11:11:55
<u>S12955</u> U USPT ('6780374')!.PN. and cool\$3 and fluid\$3 and (contorl\$3 or computer\$2 or pressur\$3 or inject\$3)	2004-10- 25 11:11:40
<u>S12954</u> U USPT ('6780374')!.PN. and cool\$3 and fluid\$3	2004-10- 25 11:06:37
<u>S12953</u> U USPT ('6780374')!.PN. and heat\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and electric\$4	2004-10- 25 10:35:15
<u>S12952</u> U USPT ('6780374')!.PN. and thermal\$2 near (conducti\$3 or	2004-10-

		conductanc\$3) and heat\$3 and fluid\$2	21 20:37:25
<u>S12951</u>	<u>U</u>	USPT ('6780374')!.PN. and resistiv\$4 and (electrical\$3 or thermal\$2) near resistiv\$4 and heat\$4 and cool\$4	2004-10-21 20:36:34
<u>S12950</u>	<u>U</u>	USPT ('6780374')!.PN. and thermal\$2 near (conducti\$3 or conductanc\$3) and heat\$3	2004-10-21 20:01:25
<u>S12949</u>	<u>U</u>	USPT ('6780374')!.PN. and cool\$3 and 633 and 565 and 570 and thermal\$2 near (conducti\$3 or conductanc\$3) and (conduct\$4 or conductanc\$3)	2004-10-21 19:57:47
<u>S12948</u>	<u>U</u>	USPT ('6780374')!.PN. and cool\$3 and 633 and 565 and 570	2004-10-21 14:24:33
<u>S12947</u>	<u>U</u>	USPT ('6780374')!.PN. and cool\$3	2004-10-21 14:20:15
<u>S12946</u>	<u>U</u>	USPT ('6780374')!.PN. and cool\$3	2004-10-21 14:20:00
<u>S12945</u>	<u>U</u>	USPT ('6780374')!.PN. and heat\$3	2004-10-21 14:02:48
<u>S12944</u>	<u>U</u>	USPT ('6780374')!.PN. and heat\$3	2004-10-21 14:02:20
<u>S12943</u>	<u>U</u>	USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and thermal\$2 near (conducti\$3 or conductanc\$3) and (conducti\$3 or conductanc\$3)	2004-10-21 13:26:46
<u>S12942</u>	<u>U</u>	USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4 and cool\$4 near (assembly or layer or area of surface\$3) and heat\$3 and cool\$3	2004-10-21 12:35:40
<u>S12941</u>	<u>U</u>	USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4 and cool\$4 near (assembly or layer or area of surface\$3)	2004-10-21 12:34:01
<u>S12940</u>	<u>U</u>	USPT ('6780374' '6353209' '6740853' '6022418')!.PN. and (electrical\$3 or thermal\$2) near resistiv\$4	2004-10-21 12:32:43
<u>S12939</u>	<u>U</u>	USPT 6780374[uref]	2004-10-21 11:06:17

S12938 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and (electrical\$3 or thermal\$2) near resistiv\$4 and heat\$4 and cool\$4 near (assembly or layer or area of surface\$3) and gap\$3 10-21 09:00:45

S12937 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and (electrical\$3 or thermal\$2) near resistiv\$4 and heat\$4 and cool\$4 near (assembly or layer or area of surface\$3) and thermal\$3 near resistiv\$4 and electrical\$3 near resistiv\$4 10-21 08:42:03

S12936 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and (electrical\$3 or thermal\$2) near resistiv\$4 and heat\$4 and cool\$4 near (assembly or layer or area of surface\$3) 10-21 08:41:32

S12935 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and (electrical\$3 or thermal\$2) near resistiv\$4 and heat\$4 and cool\$4 10-21 08:40:45

S12934 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and (electrical\$3 or thermal\$2) near resistiv\$4 and heat\$4 10-21 08:40:23

S12933 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and thermal\$3 near resistiv\$4 and electrical\$3 near resistiv\$4 10-21 08:22:31

S12932 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and (electrical\$3 or thermal\$2) near resistiv\$4 10-21 08:21:22

S12931 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 and thermal\$2 near resistiv\$4 10-21 08:20:29

S12930 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) and resistiv\$4 10-21 08:19:55

S12929 U USPT thermal\$2 near (processing or proces\$3 or apparatus) and 2004-wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3) 10-21 08:18:31

S12928 U USPT 219/443.1,444.1,442,400.ccls. and thermal\$2 near (processing or proces\$3 or apparatus) and wafer\$3 and 2004-10-20

thermal\$2 near (conducti\$3 or conductanc\$3)	23:32:02
<u>S12927 U USPT 438/\$.ccls.</u> and thermal\$2 near (processing or proces\$3 or apparatus) and wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3)	2004- 10-20 23:22:48
<u>S12926 U USPT 266/249,252.ccls.</u> and thermal\$2 near (processing or proces\$3 or apparatus) and wafer\$3 and thermal\$2 near (conducti\$3 or conductanc\$3)	2004- 10-20 23:22:13
<u>S12925 U USPT 266/249,252.ccls.</u>	2004- 10-20 22:42:48
<u>S12924 U USPT 219/443.1,444.1,442,400.ccls</u>	2004- 10-20 22:39:17